

Porous Spin Chucks

For Cee® Equipment

The Cee® Equipment product portfolio offers over 8,000 spin chuck designs that can accommodate a wide range of substrate sizes, shapes, or materials. In-house mechanical engineers are available to modify existing concepts or create custom spin chuck designs, per specific customer requests.

Serving the Semiconductor Industry Since 1987



BENEFITS

- Utilized for thinned substrates (< 150 μm)
- These spin chucks are constructed of a porous insert inside a recessed chuck cavity.
- This design provides an accurate centering function and additional support for the substrate.
- Genuine Cee® spin chucks guarantee optimal performance

CHUCK DESIGN

- Each porous spin chuck is custom-made to the exact specifications of the customer's substrate
- Available materials include Delrin, Kynar® (PVDF), Teflon® (PTFE), stainless steel, PEEK, and anodized aluminum
- Completely supporting the backside of the substrate while distributing vacuum across the entire porous surface

APPLICATION NOTES

- For demanding applications, use of an optional centering device ensures accurate and repeatable centering of circular substrates..
- Complete backside coverage and mitigation of potential rear side contamination.

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